

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3	(substrate near "process chamber") and (HCD and "hexachlorodisilane") and gas and silicon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:13
S2	24	(substrate near chamber) and (HCD or "hexachlorodisilane") and gas and silicon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/19 08:43
S3	14	(substrate near "process chamber") and (HCD or "hexachlorodisilane") and gas and silicon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/19 08:51
S4	1	(substrate near "process chamber") and (HCD or "hexachlorodisilane") and gas and silicon and hydrogen and germanium and phosphor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/19 08:53
S6	4	(substrate near "process chamber") and (HCD or "hexachlorodisilane") and gas and silicon and hydrogen and germanium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/19 08:53
S7	11	(substrate near "process chamber") and (HCD or "hexachlorodisilane") and gas and silicon and hydrogen	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 15:08
S8	114840	(substrate or semiconductor or wafer) near8 chamber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:14
S9	16269	((anneal\$4 or heat\$4) near4 (substrate or semiconductor or wafer)) near8 chamber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:15

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S10	21	((anneal\$4 or heat\$4) near4 (substrate or semiconductor or wafer)) near8 chamber and "HCD"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:15
S11	6	((anneal\$4 or heat\$4) near4 (substrate or semiconductor or wafer)) near8 chamber and ("HCD" near4 chamber)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:16
S12	6	((anneal\$4 or heat\$4) near4 (substrate or semiconductor or wafer)) near8 chamber and ("HCD" near4 chamber) and (("SiGe" or "silicon germanium" or silicon or "Si") near4 film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/23 11:17